Valence Band Structure and Photoluminescence Spectra in Strained-Layer GaInAs/GaInAs(P) MQW

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[Abstract] Photoluminescence (PL) spectra of strained-layer MQW's were measured. PL peak energy corresponding to electron- heavy-hole (e-hh) recombination has almost the same coefficient dE_{Peak}/dT as bulk semiconductors of GaAs and InAs. Furthermore, the dE_{Peak}/dT for electron- light-hole (e-lh) was obtained for the first time using tensile-strained MQW structures. The PL peak energy of the e-lh has less dependence on temperature than that of the e-hh.

[Introduction] Tensile-strained-barrier (TSB) structure, Ga_{0.47}In_{0.53}As/Ga_xIn_{1-x}As has been proposed to control the mode gain difference between TE and TM modes.1),2) A polarization-insensitive (<0.5 dB) high-gain (27.5 dB) traveling wave optical amplifier was achieved using a TSB structure³). In this report, the valence band structure and electronlight-hole (e-lh) recombination process clarified by considering are the dependence temperature of photoluminescence in the TSB structure comparing with electron- heavy-hole recombination in strained-layer MQW's.

[Experiments and Results] Strainedlayer MQW structures were epitaxially grown by low-pressure (50 Torr) MOVPE on Sn-doped InP (100) substrates in a vertical reactor. The lattice mismatch $\varepsilon = [(a-a_0)/a_0] \times 100$ (%) was determined through the double crystal XD where a_0 is the lattice constant of the InP substrate and a is that of the mismatched layer. Ga content x was estimated from the value of the lattice constant a.

The TSB structure is as follows. Well layers are 5-nm-thick Ga_{0.47}In_{0.53}As. Strained barriers are 5-nm-thick $Ga_{0.72}In_{0.28}As$. The resulting band diagram structure is shown in Fig.1. The schematic band diagram of the TSB structure calculated following H. Asai and K. Oe²),4) is shown in Fig. 1. The light-hole band



Fig.1. Band Diagram of the TSB Structure.

energy level in the barrier layers is made less than that of the heavy-hole energy in the well layers by biaxial tension in the barrier layers. This TSB structure has a "type II" band structure for light-holes and a "type I" structure for the heavyholes as shown in Fig. 2. However, because a band discontinuity of the light hole is very small²), light-hole are not localized in the tensile-strained-barrier layers.



Fig.2. PL spectra of the TSB MQW at 200, 250 and 300 K.

MQW structures which were used in this measurement are shown in Table 1. Two of the samples are a lattice-matched MQW and a compressive-well MQW which have GalnAsP (λ_0 =1.3 µm) barriers of 10nm-thick and GaInAs wells. A lattice mismatch of the latter sample was $\varepsilon = +1.5$ %. Another sample has tensile-strainedwells of GalnAs (ϵ =-1 %) with GalnAsP $(\lambda_q=1.2 \ \mu m)$ barriers of 10-nm-thick. Well controlled to obtain width were а desirable PL wavelength of 1.55 µm.

PL spectra of the TSB structure at 200, 250, and 300 K are shown in Fig. 2. The two peaks observed in Fig. 2 correspond to transitions from the heavyhole band and the light-hole band to the respectively. As conduction band. decreased. the PL temperature is photoluminescence intensity of e-lh



Fig.3. Temperature dependence of PL peak energies corresponding to e-hh recombination.

becomes stronger. The e-hh spectrum was too weak to be distinguished below 150 K. This comes from thermal distribution of holes because the Ih-level exists lower than hh-level.

Temperature dependences of the peak energies of the spectra are shown in Fig.3 corresponding to e-hh recombination in the three type samples of a latticea compressive-well matched. and а tensile-barrier MQW's. All of the samples shows similar dE/dT coefficient, such as -2.95x10-4, -2.72x10-4 and -3.29x10-4 eV/K, respectively. This value is very close to that of bulk GaAs (-3.95x10-4 eV/K)⁴⁾ and bulk InAs (-3.3x10⁻⁴ eV/K)⁵⁾. that the This means e-hh energy difference directly reflects the band gap energy dependence of GaxIn1-xAs on temperature. Photoluminescence peak

MQW Structure	Barrier		Well		2 2 (1172)
	Composition	Thickness	Composition	Thickness	λει (μm)
A) Lattice-matched	GalnAsP (λ ₉ =1.3 μm)	10 nm	Ga _{0.47} In _{0.53} As	5 nm x 10 layers	1.56
B) Compressive-well	GalnAsP (λ _g =1.3 μm)	10 nm	Ga _{0.32} In _{0.68} As (E=+1.0%)	3 nm x 10 layers	1.55
C) Tensile-well	GalnAsP (λ _g =1.2 μm)	10 nm	Ga _{0.54} In _{0.46} As (E=-0.5%)	8 nm x 6 layers	1.50
D) Tensile-barrier	Ga _{0.72} In _{0.28} As (E=-1.7%)	5 nm	Ga _{0.47} In _{0.53} As	5 nm x 10 layers	1.59

Table 1. Structures of MQW Samples



Fig.4. Temperature dependence of PL peak energies corresponding to e-lh recombination.

energy dependence on temperature are shown in Fig.4 corresponding to e-lh recombination in the two samples, such as a tensile-well and tensile-barrier MQW. Thev have a less dependence on temperature than the e-hh recombination at values of (dE/dT)e-lh=-9.53x10-5, -2.5x10⁻⁴ eV/K, respectively. In the lower temperature region, the same peak-energy shift saturation was observed as unsemiconductors. strained bulk dF/dTcoefficients are assembled in Table 2. In the TSB structure, PL spectra from both e-hh and e-lh recombination can be observed.

	dE _{peak} /dT (meV/K)		
MQW structure	e-hh	e-lh	
A) Lattice-matched	-2.95x10 ⁻⁴	7. 	
B) Compressive-well	-2.72x10 ⁻⁴	· <u> </u>	
C) Tensile-well		-9.53x10-5	
D) Tensile-barrier	-3.29x10 ⁻⁴	-2.52x10 ⁻⁴	
GaAs ref.4)	-3.95x10 ⁻⁴	*	
bulk InAs ref.5)	-3.3 x10 ⁻⁴		

Table.2. PL peak energy dependence on temperature in strained-layer MQW structures [Summary] Photoluminescence dependence on temperature of strainedlayer MQW structures were measured. The e-hh shows a similar behavior to bulk semiconductors, however, the e-lh represents less dependence on temperature.

[References]

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